

IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) An assembly configured to be coupled to components of a plasma reactor, the assembly comprising:

an electrostatic shield; and

at least one spira-shield electrically connected to the electrostatic shield; and

a process tube,

wherein the electrostatic shield is coupled to the process tube such that the electrostatic shield resides around the process tube and, at times of process tube removal from the plasma reactor, the electrostatic shield is extracted with the process tube, and

wherein the at least one spira-shield grounds the electrostatic shield.

2. (Previously Presented) An assembly configured to be coupled to components of a plasma reactor, the assembly comprising:

an electrostatic shield;

at least one spira-shield electrically coupled to the electrostatic shield; and

a process tube,

wherein the electrostatic shield is coupled to the process tube such that the electrostatic shield resides around the process tube and, at times of process tube removal from the plasma reactor, the electrostatic shield is extracted with the process tube.

3. (Previously Presented) An assembly configured to be coupled to components of a plasma reactor, the assembly comprising:

- an electrostatic shield;
- a process tube,

wherein the electrostatic shield is coupled to the process tube such that the electrostatic shield resides around the process tube and, at times of process tube removal from the plasma reactor, the electrostatic shield is extracted with the process tube; and

at least one insulating spacer located between the electrostatic shield and an end of the process tube.

4. (Original) The assembly of claim 3, wherein the at least one insulating spacer positions the electrostatic shield from the process tube, at their closest point, by a maximum distance of one inch.

5. (Original) The assembly of claim 3, wherein the at least one insulating spacer positions the electrostatic shield from the process tube, at their closest point, by approximately 3/8 of an inch

6. (Original) The assembly of claim 1, wherein the electrostatic shield is attached to the process tube.

7. (Original) An assembly configured to be coupled to components of a plasma reactor, the assembly comprising:

- a process tube, and
- an electrostatic shield patterned directly on the process tube.

8. (Original) The assembly of claim 7, wherein the electrostatic shield is patterned directly on the process tube using at least one of sputtering, evaporation or metal vapor deposition.

9. (Original) The assembly of claim 8, wherein the electrostatic shield is patterned on the process tube also using a plating process that increases a thickness of the electrostatic-shield.

10. (Previously Presented) An assembly configured to be coupled to components of a plasma reactor, the assembly comprising:

a process tube;  
an electrostatic shield patterned directly on the process tube; and  
at least one spira-shield electrically coupled to the electrostatic shield.

11. (Currently Amended) An assembly configured to be coupled to components of a plasma reactor, the assembly comprising:

a process tube; and  
an electrostatic shield made from a flex-print material; and  
at least one spira-shield electrically connected to the electrostatic shield,  
wherein the electrostatic shield is coupled to the process tube such that the electrostatic shield resides around the process tube and, at times of process tube removal from the plasma reactor, the electrostatic shield is extracted with the process tube, and  
wherein the at least one spira-shield grounds the electrostatic shield.

12. (Previously Presented) The assembly of claim 11, wherein the flex-print material is a polyimide film.

13. (Previously Presented) An assembly configured to be coupled to components of a plasma reactor, the assembly comprising:

a process tube; and

an electrostatic shield made from a flex-print material,

wherein the electrostatic shield is coupled to the process tube such that the electrostatic shield resides around the process tube and, at times of process tube removal from the plasma reactor, the electrostatic shield is extracted with the process tube, and

wherein the electrostatic shield is implemented between two sheets of the flex-print material except on a top and bottom to allow for contacts with a spira-shield.

14. (Previously Presented) An assembly configured to be coupled to components of a plasma reactor, the assembly comprising:

a process tube;

an electrostatic shield made from a flex-print material; and

at least one spira-shield electrically coupled to the electrostatic shield,

wherein the electrostatic shield is coupled to the process tube such that the electrostatic shield resides around the process tube and, at times of process tube removal from the plasma reactor, the electrostatic shield is extracted with the process tube.

15. (Canceled)

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16. (Currently Amended) The assembly of claim 11, wherein the electrostatic shield and the process tube are bonded together.

17. (Previously Presented) A method of fabricating an assembly including a housing, a process tube and an electrostatic shield, the method comprising:

coupling the process tube to an electrostatic shield, within the electrostatic shield, to form the assembly; and

electrically coupling the electrostatic shield to a housing through a spiral-shield.

18. (Previously Presented) A method of fabricating an assembly including both a process tube and an electrostatic shield, the method comprising:

providing a the process tube; and

patternning the electrostatic shield onto the process tube using at least one of sputtering, evaporation or metal vapor deposition.

19. (Original) The method of claim 18, whercin the patterning includes a plating process that increases a thickness of the electrostatic-shield.

20. (Previously Presented) A method of fabricating an assembly including both a process tube and an electrostatic shield, the method comprising:

providing a the process tube;

patternning the electrostatic shield onto the process tube using at least one of sputtering, evaporation or metal vapor deposition; and

electrically coupling the electrostatic shield to at least one spiral-shield.

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21. (Canceled)

22. (Previously Presented) The assembly of claim 1, wherein the process tube is coupled to the electrostatic shield such that the process tube positions the electrostatic shield within the plasma reactor.

23. (Previously Presented) The assembly of claim 11, wherein the process tube is coupled to the electrostatic shield such that the process tube positions the electrostatic shield within the plasma reactor.